

WEST Search History

DATE: Friday, September 29, 2006

Hide?	Set Name	Query	Hit Count
		<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L19	((HF dip) same (RCA clean) same (NF3 clean) same (hydrogen bake) same (polysilicon deposition))	0
<input type="checkbox"/>	L18	((HF dip) same (RCA clean) same (NF3 clean) same (hydrogen bake) same (polysilicon deposition)) AND @pd>20060927	0
<input type="checkbox"/>	L17	((decontaminat\$ or remov\$) and ((hydrogen-adsorbed layer) or (hydrogen termination)) and forming and (nitrogen fluoride))	5
<input type="checkbox"/>	L16	((integrated circuit) or semiconductor) with (removing or cleaning) with forming with hydrogen termination	0
<input type="checkbox"/>	L15	((integrated circuit) or semiconductor) with (removing or cleaning) with forming with hydrogen termination AND @pd>20060927	0
<input type="checkbox"/>	L14	((integrated circuit) or semiconductor with removing or cleaning) with (forming with hydrogen termination)) AND @pd>20060927	0
<input type="checkbox"/>	L13	((integrated circuit) or semiconductor) with (removing or cleaning)) AND @pd>20060927 AND @pd>20060929	0
<input type="checkbox"/>	L12	((HF dip) and (RCA clean) and (NF3 clean) and (hydrogen bake) and (polysilicon deposition))	1
<input type="checkbox"/>	L11	((integrated circuit) or (semiconductor)) with (removing or cleaning)	42424
<input type="checkbox"/>	L10	((integrated circuit) or semiconductor) with (removing or cleaning)) AND @pd>20060927 AND @pd>20060929	0
<input type="checkbox"/>	L9	((exposing with (nitrogen containing gas) or (nitrogen fluoride) with (integrated circuit) or semiconductor) same (forming with hydrogen termination))	17
<input type="checkbox"/>	L8	((HF dip) and (RCA clean) and (NF3 clean) and (hydrogen bake) and (polysilicon deposition))	1
<input type="checkbox"/>	L7	((HF dip) and (RCA clean) and (NF3 clean) and (hydrogen bake) and (polysilicon deposition)) AND @pd>20060927	0
		<i>DB=EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L6	((HF dip) and (RCA clean) and (NF3 clean) and (hydrogen bake) and (polysilicon deposition)) AND @pd>20060927	0
		<i>DB=PGPB,USPT; PLUR=YES; OP=ADJ</i>	
<input type="checkbox"/>	L5	((exposing with (nitrogen containing gas) or (nitrogen fluoride) with (integrated circuit) or semiconductor) same (forming with hydrogen termination)) AND @pd>20060927	0
<input type="checkbox"/>	L4	((exposing) with ((nitrogen containing gas) or (nitrogen fluoride)) with ((integrated circuit) or semiconductor)) AND @pd>20060927	0
<input type="checkbox"/>	L3	((integrated circuit) or semiconductor) with (removing or cleaning)) AND	77

<input type="checkbox"/>	L2	@pd>20060927 (((integrated circuit) or semiconductor) with (removing or cleaning)) AND @pd>20060927	77
<input type="checkbox"/>	L1	((exposing) with ((nitrogen containing gas) or (nitrogen fluoride)) with ((integrated circuit) or semiconductor)) AND @pd>20060927	0

END OF SEARCH HISTORY